

# Carbon Dioxide Trap

## WARNINGS

Maximum pressure 68.9 bar/6890 kPa (1000 psig).

Wear eye protection and use caution when working with pressurized systems.

When using a high-pressure gas source, overpressure protection must be provided.

Do not open filter, even after use.

Contains sodium hydroxide NaOH. Caustic! The absorption of carbon dioxide or water by NaOH gives off heat. Use only with dry gases containing less than 1% carbon dioxide.

Do not use with moist gases or liquids.

Special precautions might be required when using hydrogen or hazardous gases. Consult local regulations and your company's safety procedures.

## Product Information

- Removes carbon dioxide from inert gases He; Ar; N<sub>2</sub>; H<sub>2</sub>; and clean dry air (CDA) to low ppb levels.
- Functions by consuming carbon dioxide in a reaction with highly dispersed NaOH on a silicate support (reaction produces water, which remains adsorbed in the purifier).
- In highly critical applications, consider using an additional moisture trap after the CO<sub>2</sub> trap as a safety measure.
- Maximum flow rate: 1300 cc/min

## Installation

### Restek Recommends:

- To ensure optimal bed packing and performance, and to minimize the likelihood of material "channeling," gas filters should be installed vertically.
- For the inlet gas to have a moisture content of less than 10 ppmv (-60 °C dew point).

The CO<sub>2</sub> Trap is delivered pre-purged with helium. Before operating any instruments, it should be purged with the gas you will be using. When connecting to a gas line, use two wrenches at each coupling. For best connections, start with freshly cut tubing in the gas line.

**Warning:** If you are using hydrogen or hazardous gas, additional special procedures may be needed. Consult your company's safety procedures.



## Questions about this or any other Restek product?

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#204-08-031 Rev. date: 12/24



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